



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Re the Application of: **Tamihide YASUMOTO**

Group Art Unit: **2813**

Serial No.: **09/995,575**

Examiner: **KIELIN, Erik J.**

Filed: **November 29, 2001**

Confirmation No.: **1497**

For: **SEMICONDUCTOR DEVICE MANUFACTURING METHOD USING METAL SILICIDE REACTION AFTER ION IMPLANTATION IN SILICON WIRING**

Attorney Docket No.: **011317**

Customer Number: **38834**

PETITION FOR EXTENSION OF TIME

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Date: February 9, 2004

Sir:

Applicants petition the Commissioner for Patents to extend the time for response to the Office Action dated September 8, 2003 for 2 months from December 8, 2003 to February 8, 2004.

Attached please find a check in the amount of \$ 1,190.00. This check includes \$ 770.00 for filing an RCE and \$ 420.00 to cover the cost of the extension for a large entity. In the event that any additional fees are due in connection with this paper, please charge our Deposit Account No. 50-2866.

Respectfully submitted,

WESTERMAN, HATTORI, DANIELS & ADRIAN, LLP

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